

Nano Technology Industrial Park at Cheorwon



Cheorwon Plasma Nano Technology Cluster

Cheorwon* Plasma Research Institute

Innovative Product utilizing a Novel Materials

Plasma Nano Technology Center provides not only Facility/Equipment but also The Technology

More than 10 companies currently licensed CPRI's nano technology for commercialization



강원도
GANGWON PROVINCE



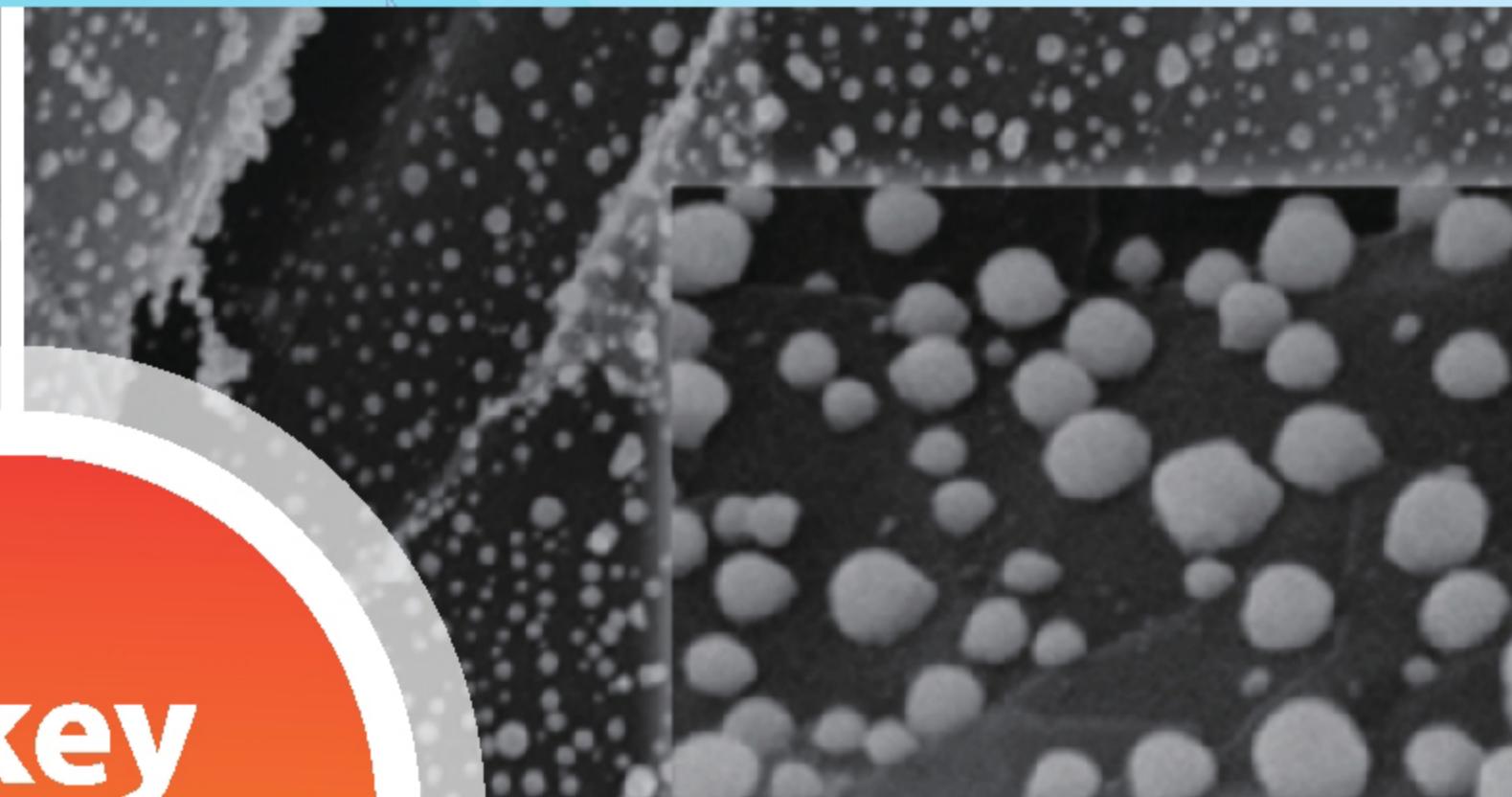
철원군
Cheorwon



1 | RF/DC Thermal Plasma (7) patents



2 | Nano Metal / Carbon Hybrid (3) materials patents



4 key
Technologies

3 | OLED Lightings (3) design patents



4 | Nano material Functionalization (4) patents



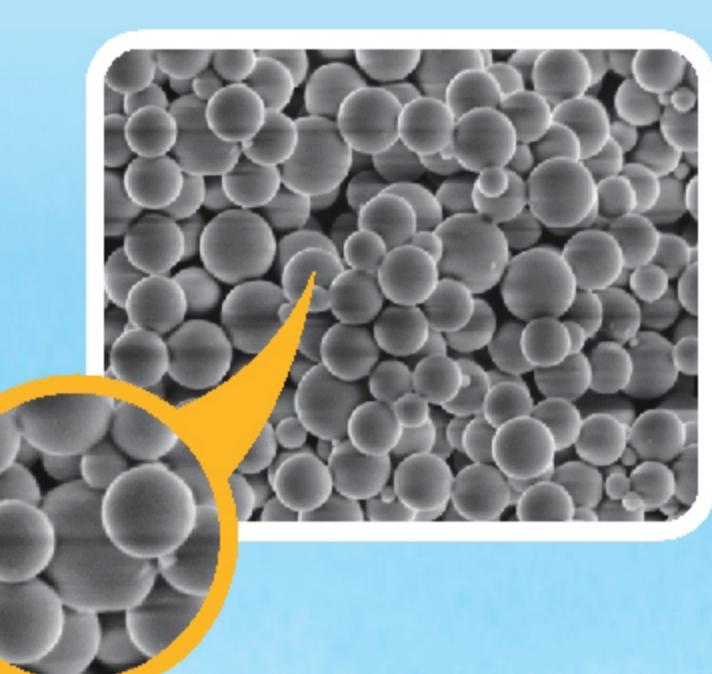
Cheorwon Plasma Research Institute

Research expertise of CPRI is a nano-materials engineering by using plasma process.

CPRI developed a mass production systems for synthesis of nano-materials.

CPRI also reported a world first commercial level production of nano metal-graphene hybrid materials (nano sized metal such as Si, Ag, Ni, Sn, Cu, Al etc. bonded to nano graphene flakes)

CPRI introduces a world first nano-powder plasma system for surface modification, functionalization, CVD of nano-materials.



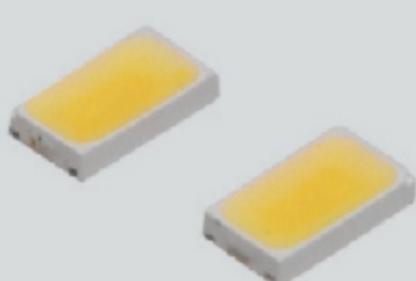
Cheorwon Plasma Nano Technology Cluster

INFOVION



dispersion equipment

ALLIX



LED Packaging

JSI



Activated Carbon

GNTNS



Coal Water Slurry &
Oil Burner System

Nanocasttech



Nano Material
production

NanoGate



Nano Magnetic Materials /
Magnetic Sensors

Nano Materials Production/Equipment Group



Nano Materials Application Group

LMS



Flexible Heat
Spreader

Kolon



OLED Penal

Changsung



EMI/Nano-Ink

CoreTech



Automobile
Injection

OCI



LIB
(Anode)

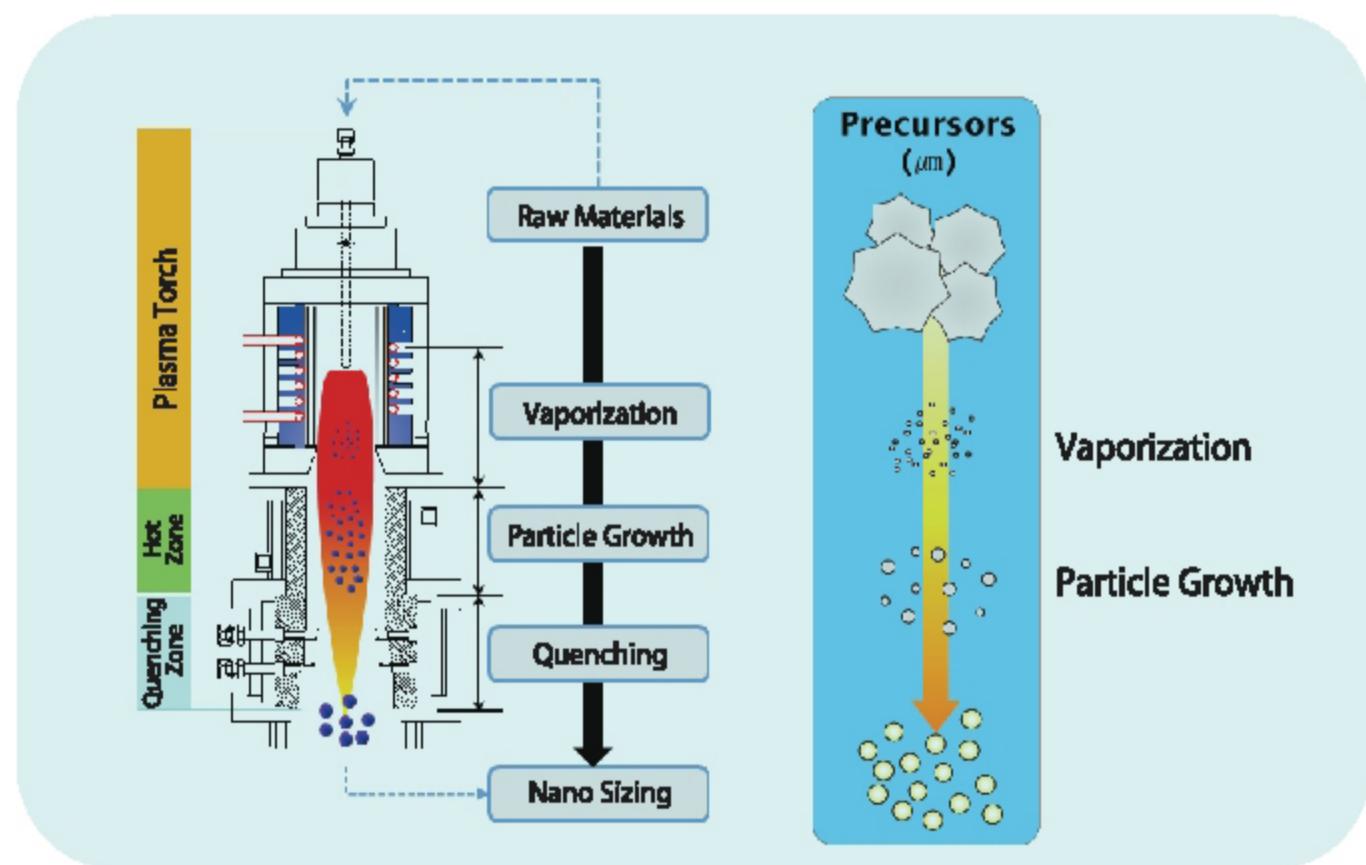
GLVISION



High CRI LED
Downlight

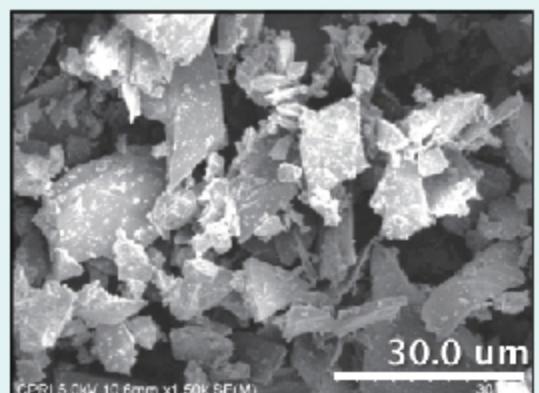
01 RF Thermal Plasma Nano Technology

■ Nano-materials synthesis

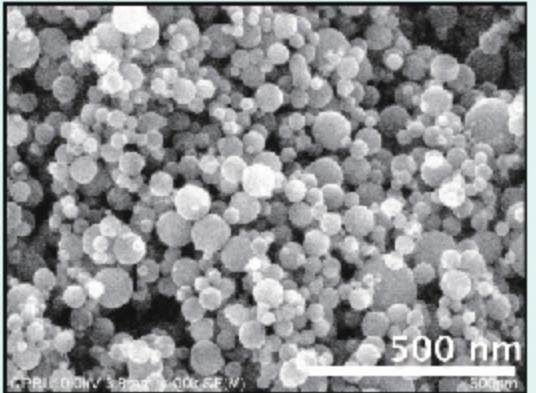


Nano Material (Si)

<raw material>



< nano material >

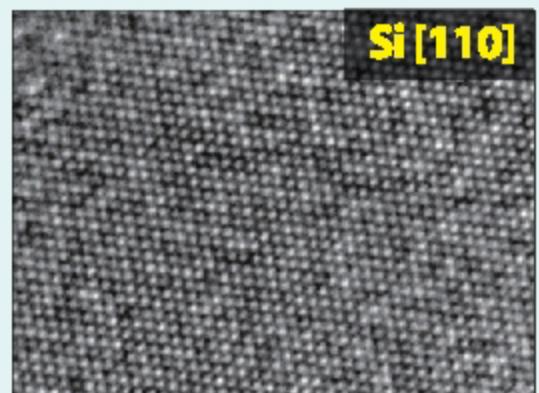


Avg. Particle Size
50 – 70 nm

Color
Brown yellow

Structure
Single crystalline

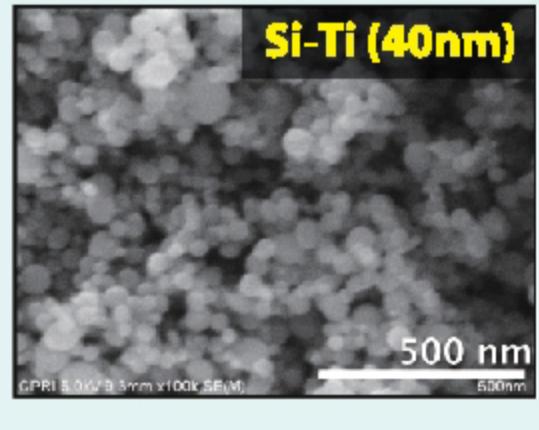
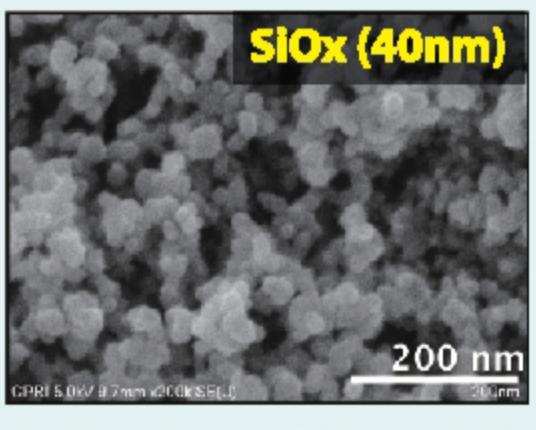
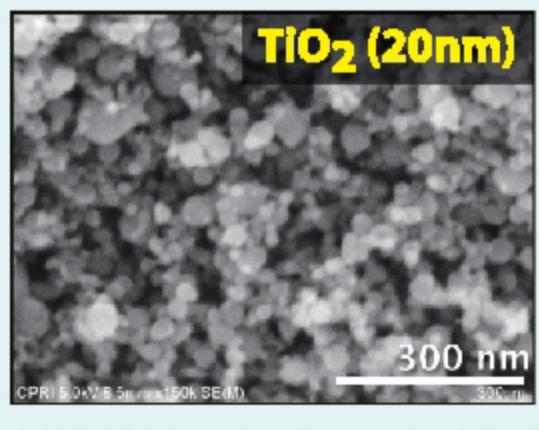
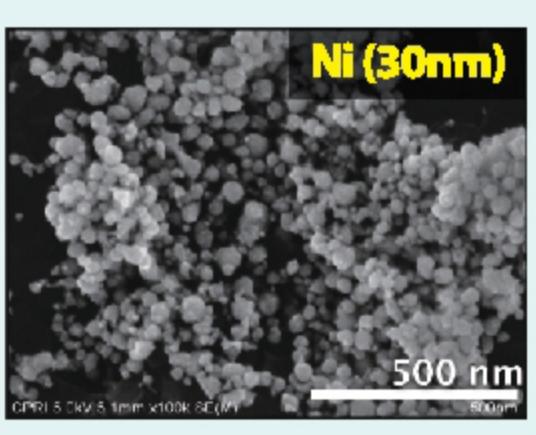
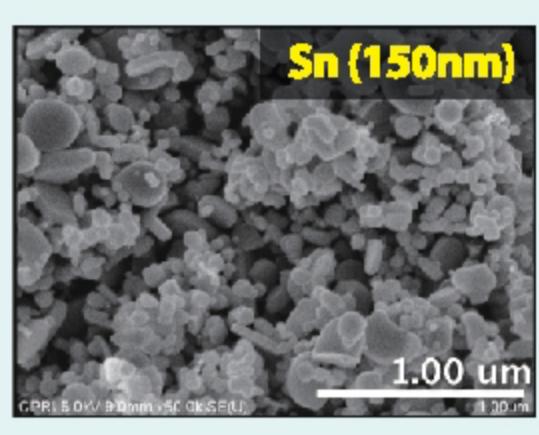
Si [110]



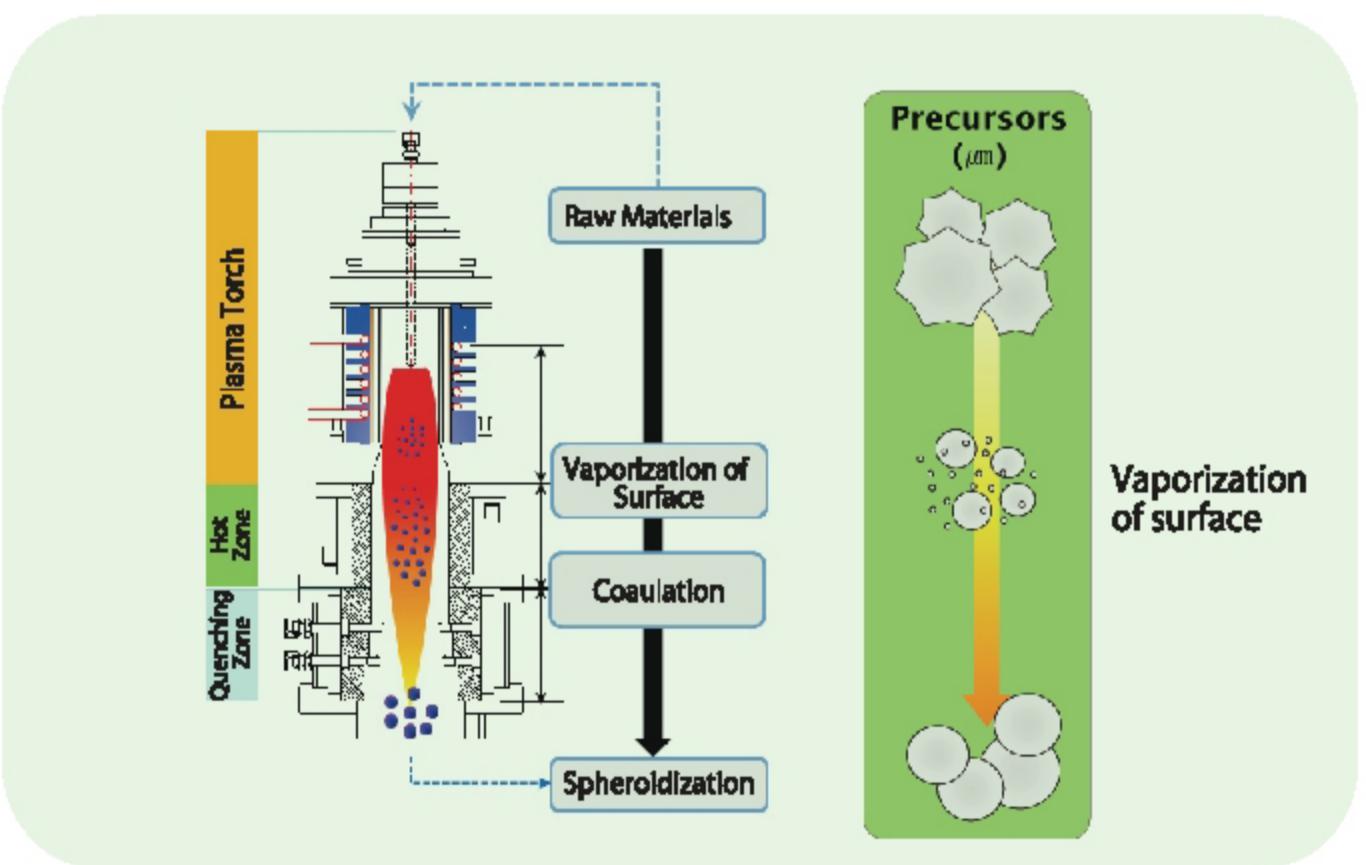
Si [112]



Others (Nano Powders)

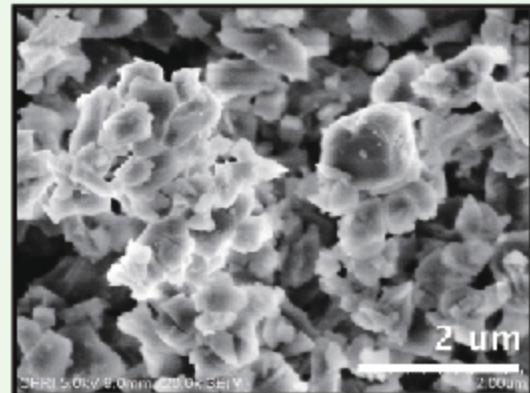


■ Spheroidization Process

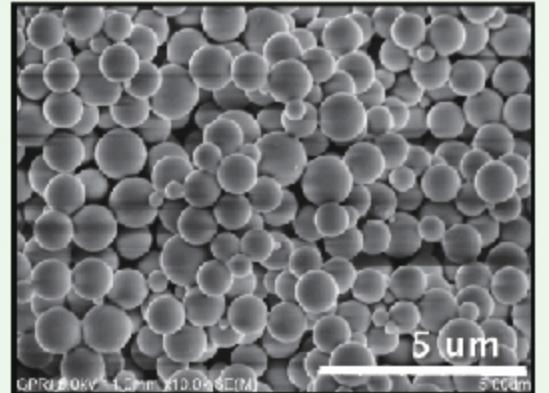


Spheroidization (Ba Glass)

<raw material>

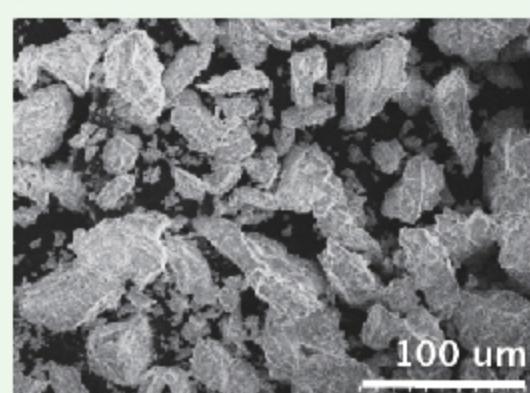


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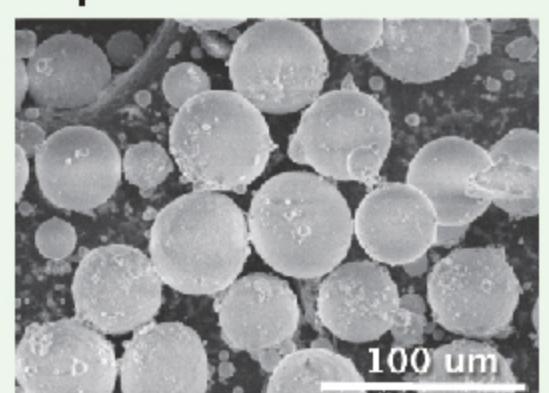


Spheroidization ($\text{SrO-Al}_2\text{O}_3$)

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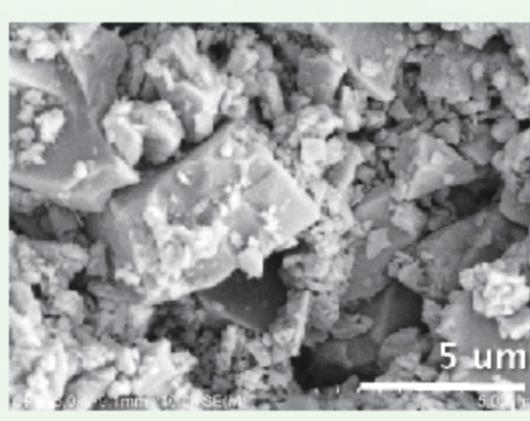


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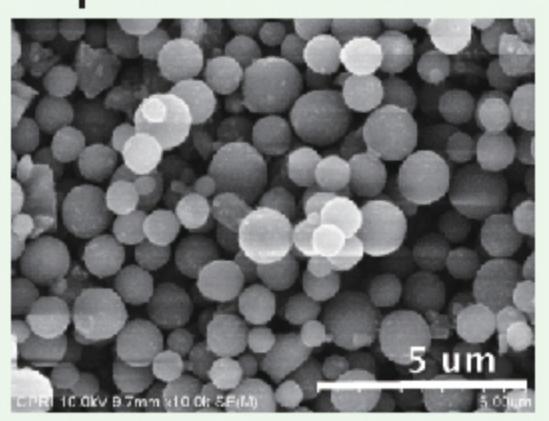


Spheroidization (Silicon)

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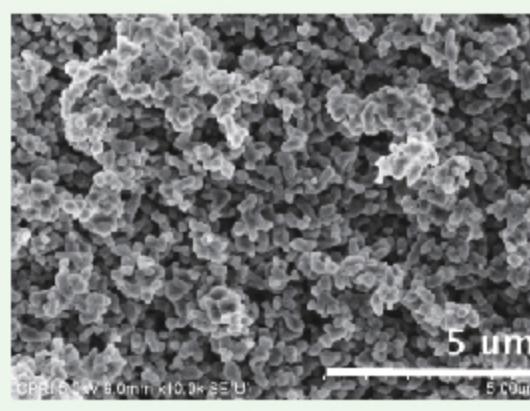


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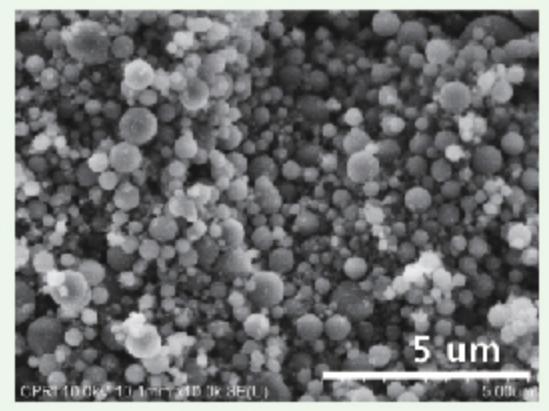


Spheroidization (Alumina, Al_2O_3)

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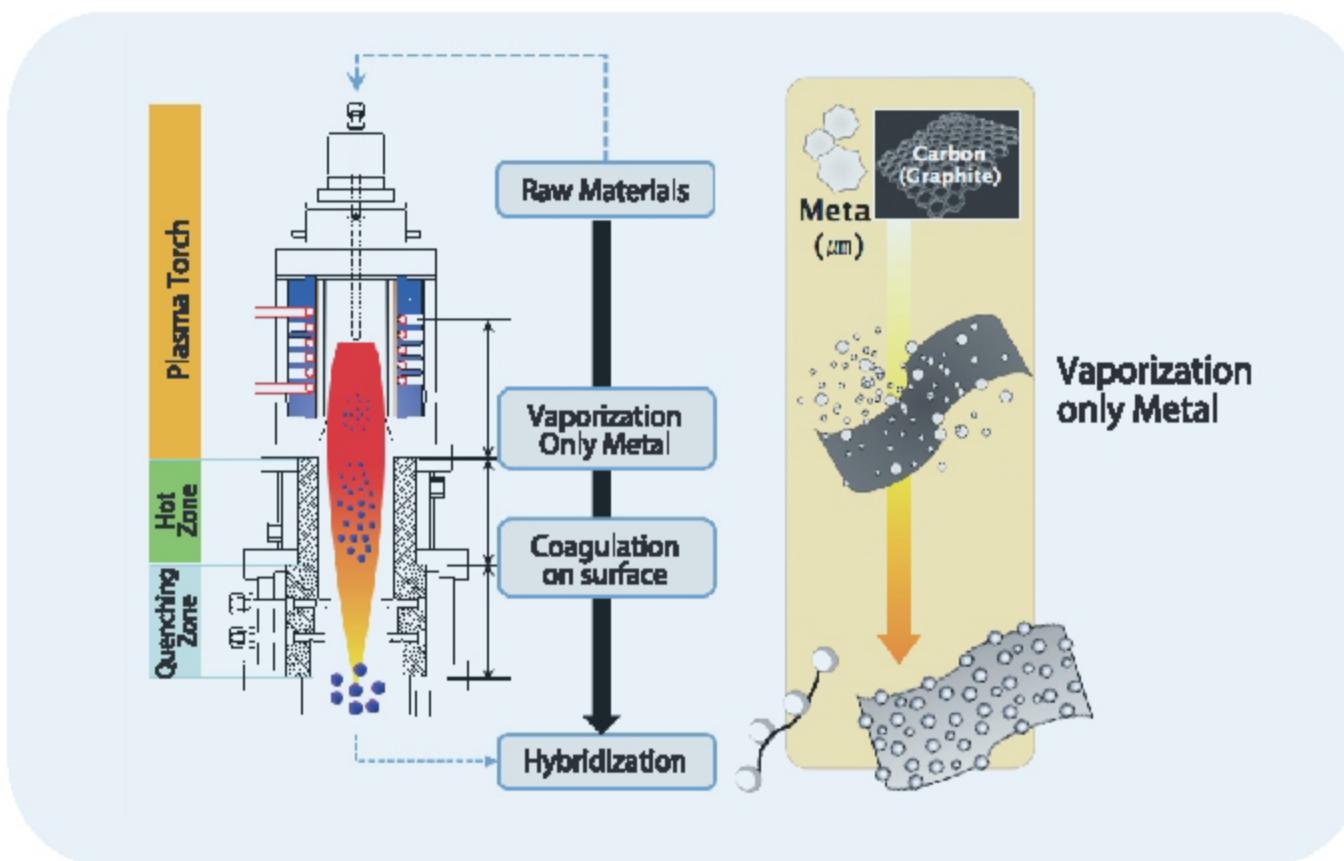


<Spheroidized material>

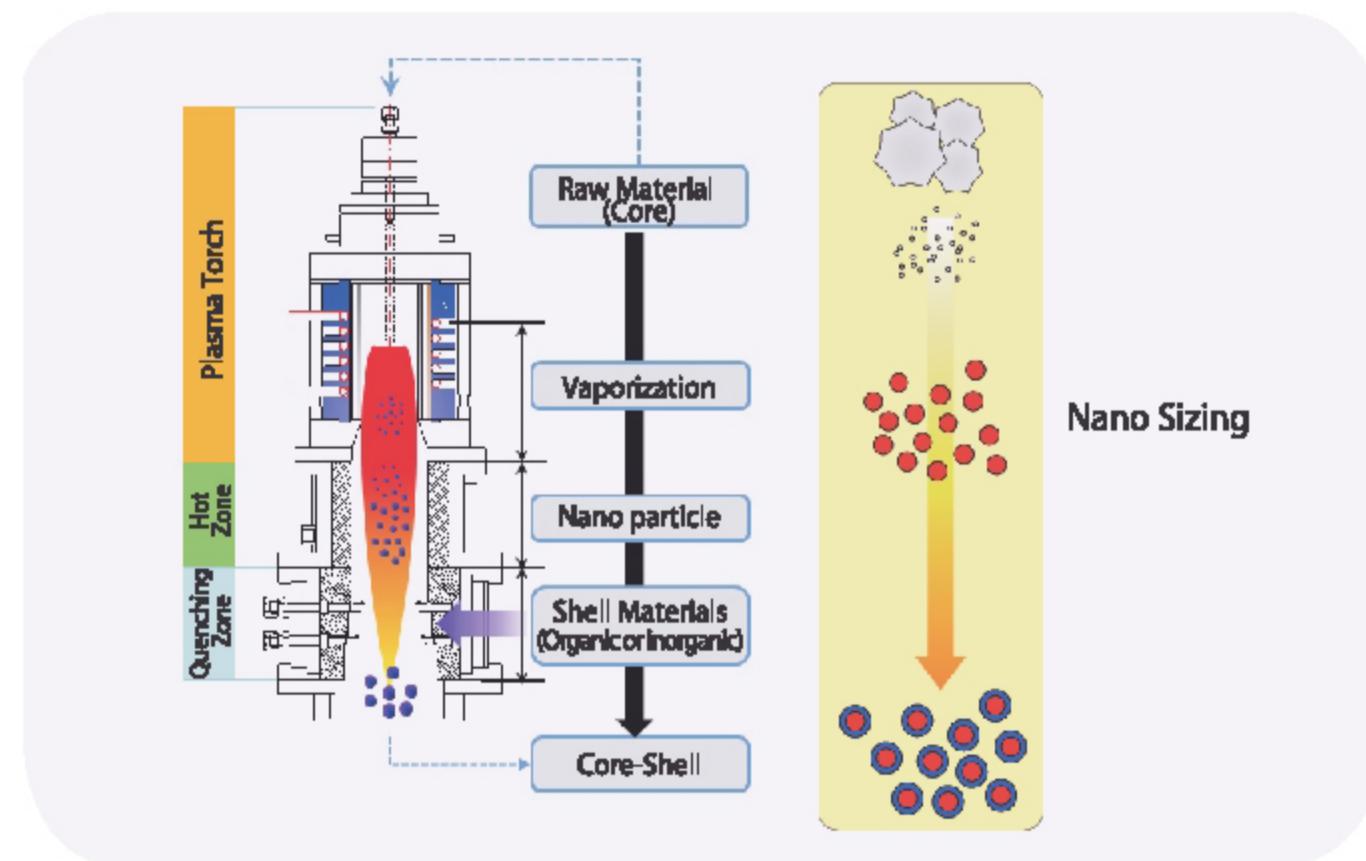


>>> RF Thermal Plasma Nano Technology

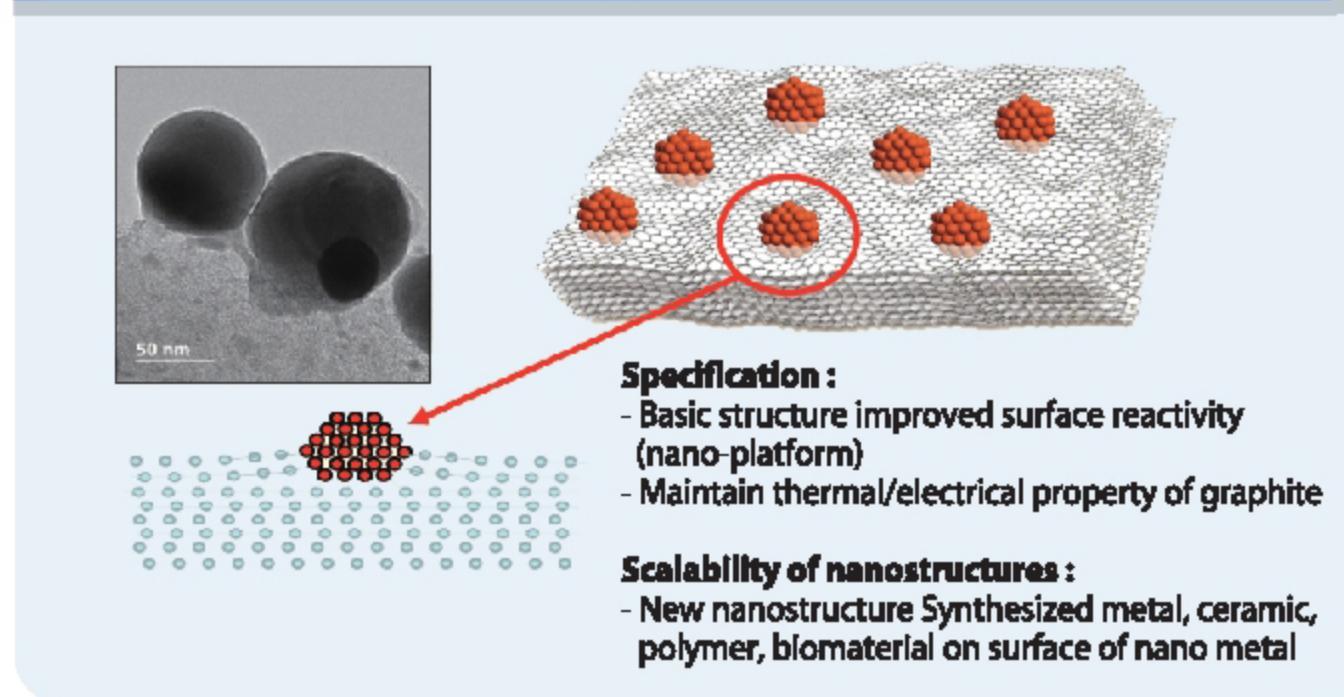
Nano-metal/Carbon Hybrid



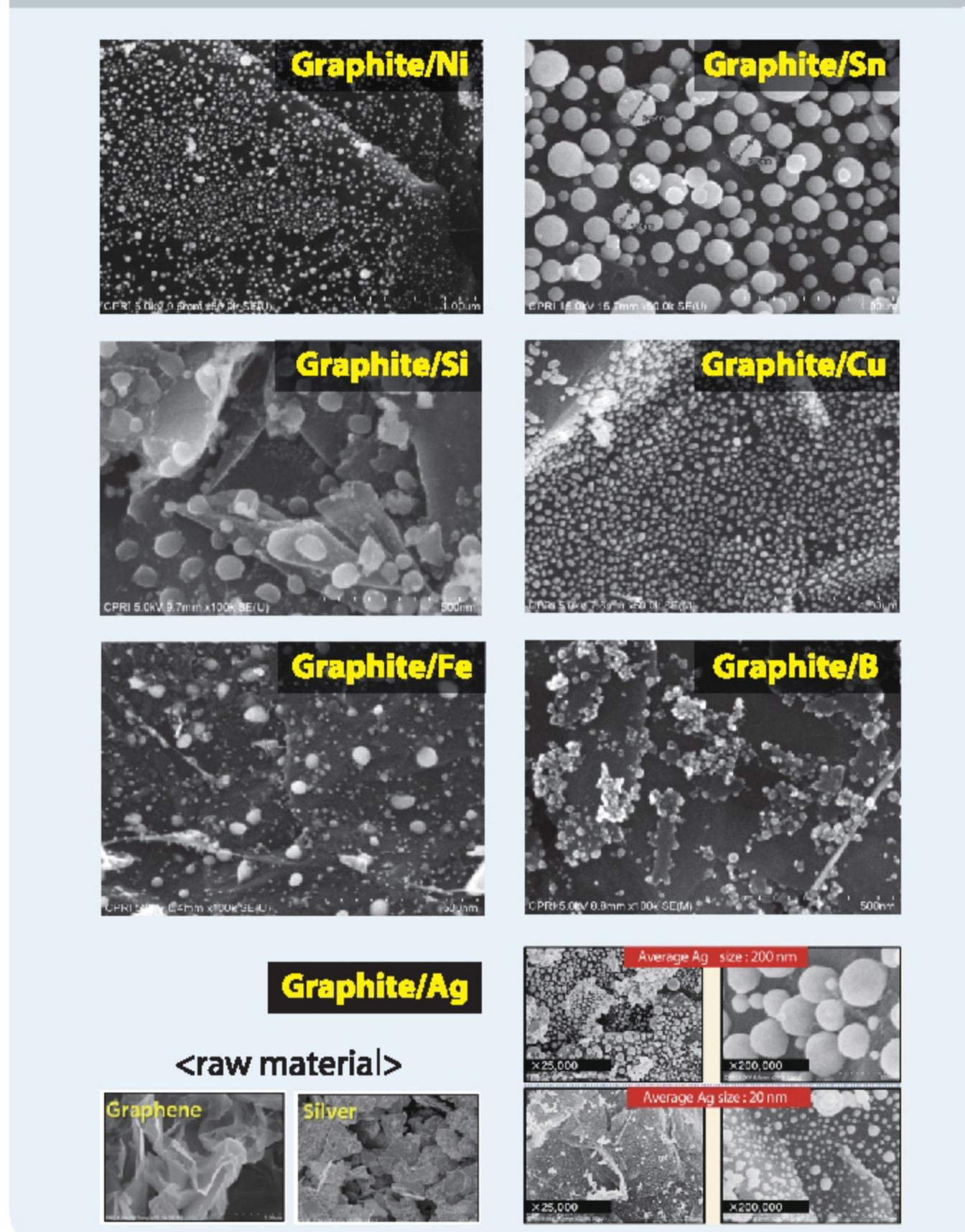
In-situ Core-Shell Process



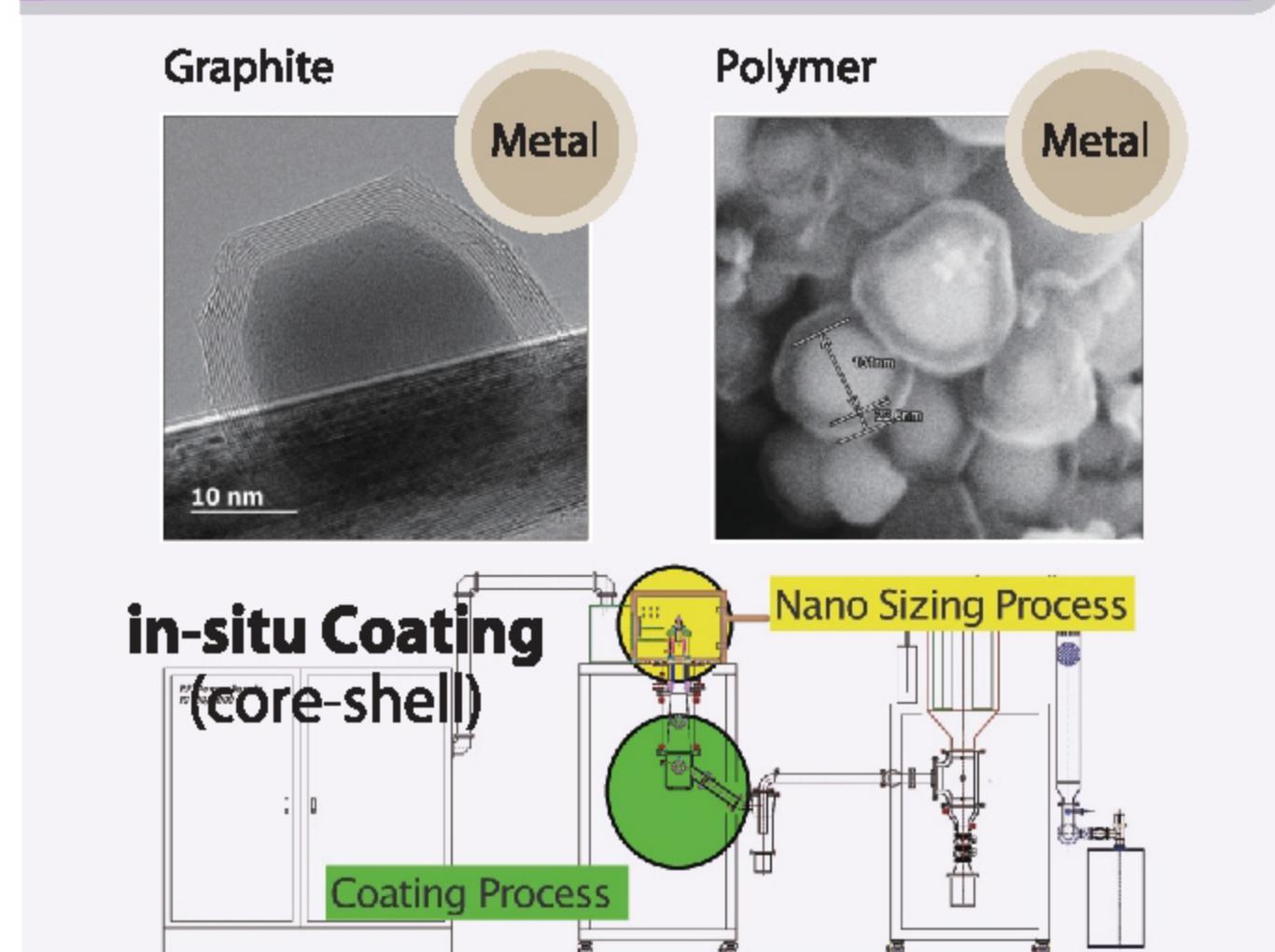
Nano Metal/Graphite Nano Platform



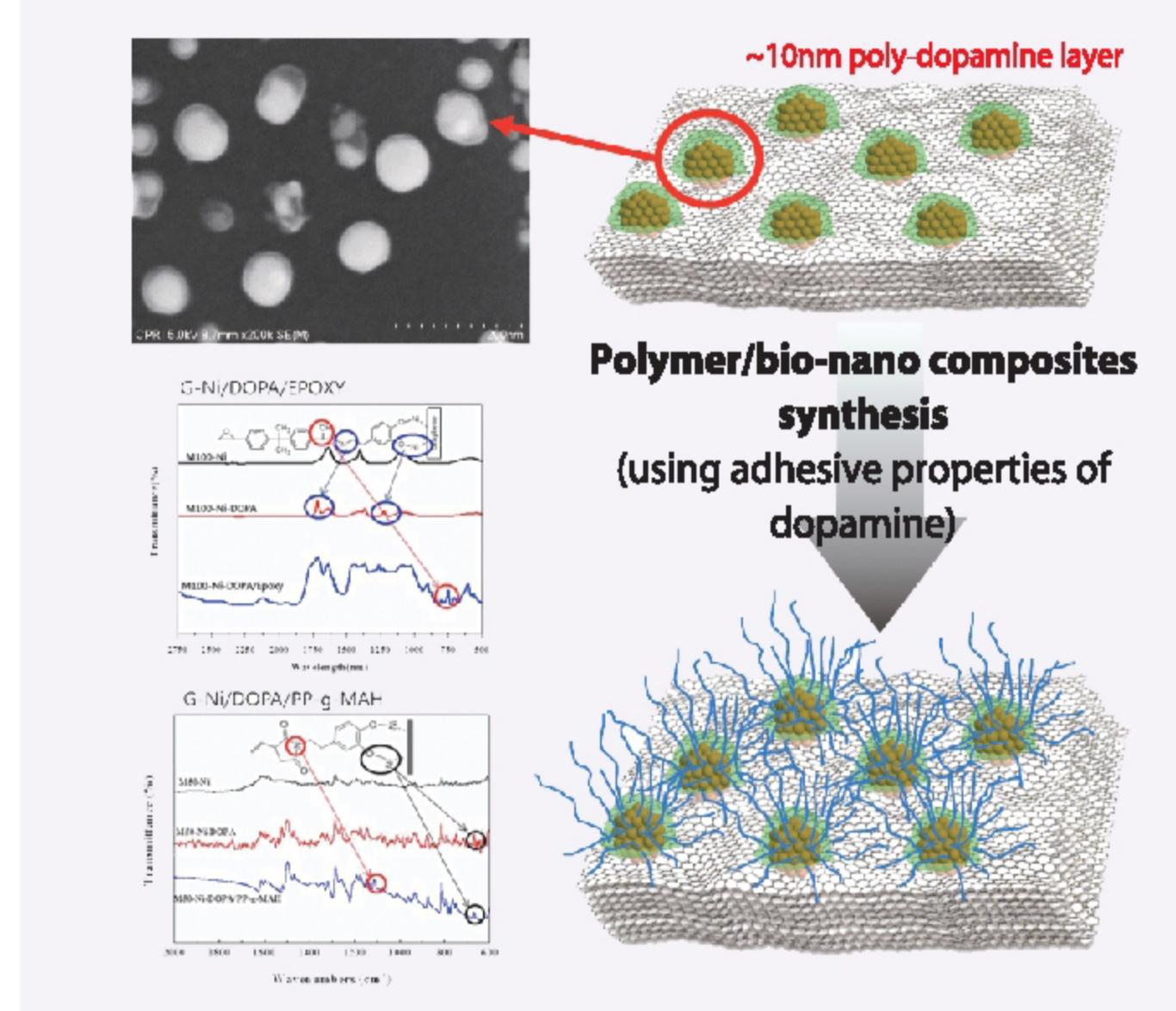
Nano-metal/Carbon Hybrid Compounds



In-situ Coating Process on nano-Metal



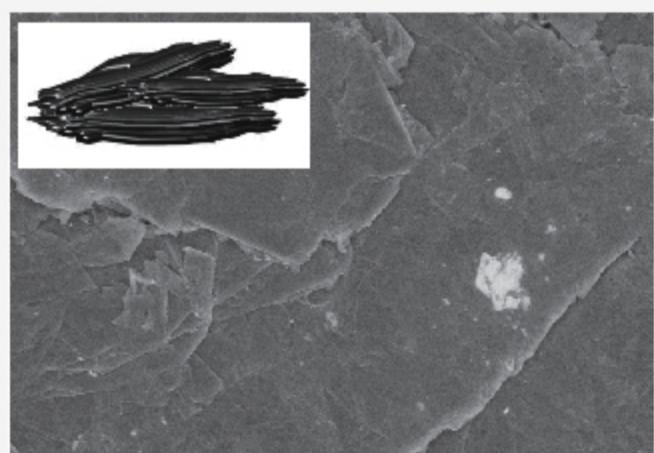
Nano-Metal / Graphite & Polymer Composite by poly-dopamine nano coating



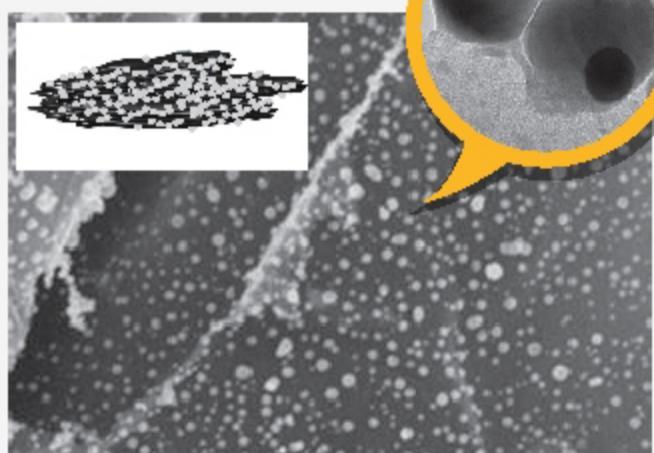
02 Nanocomposites in CPRI

Amogreentech

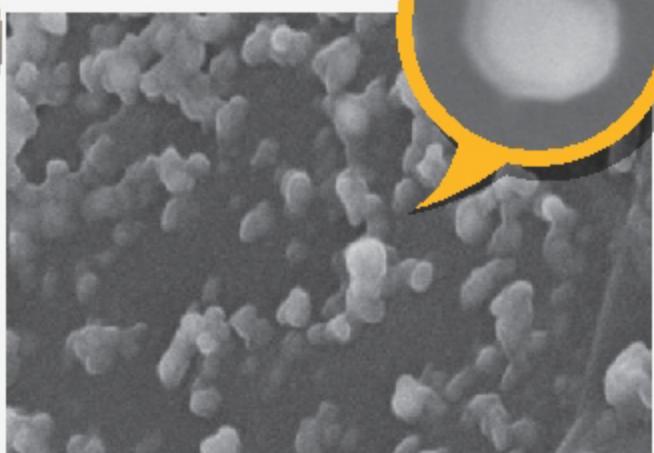
Materials



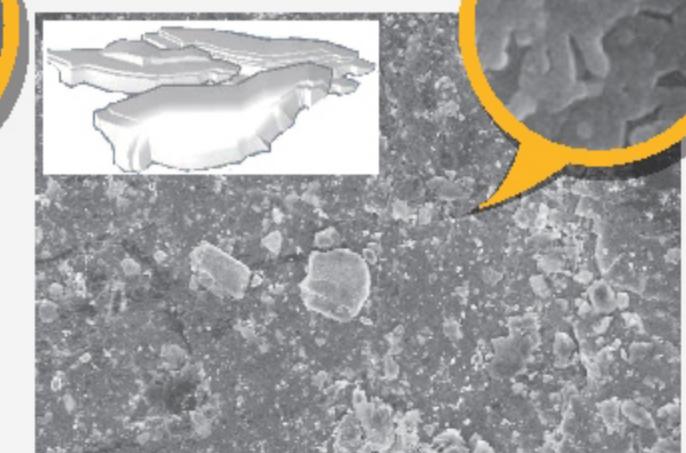
Graphite



Nano metal-Graphite



Functionalized metal-Graphite

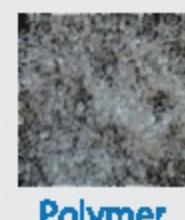


Insulated-Graphite

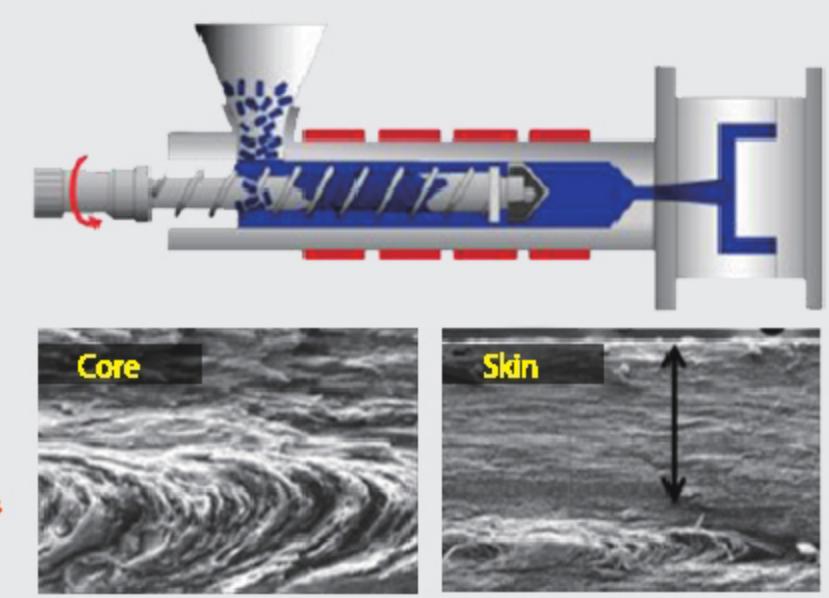
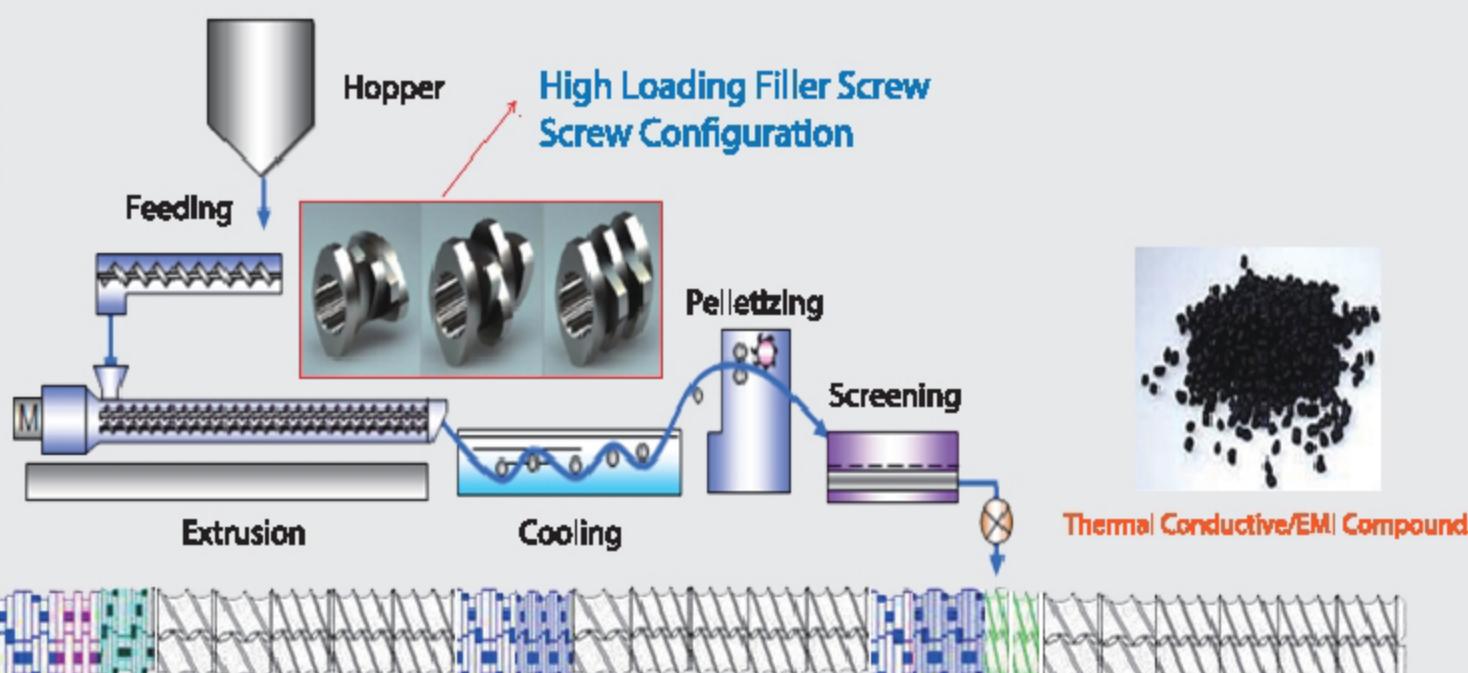
Processing



Conductive Filter



Polymer

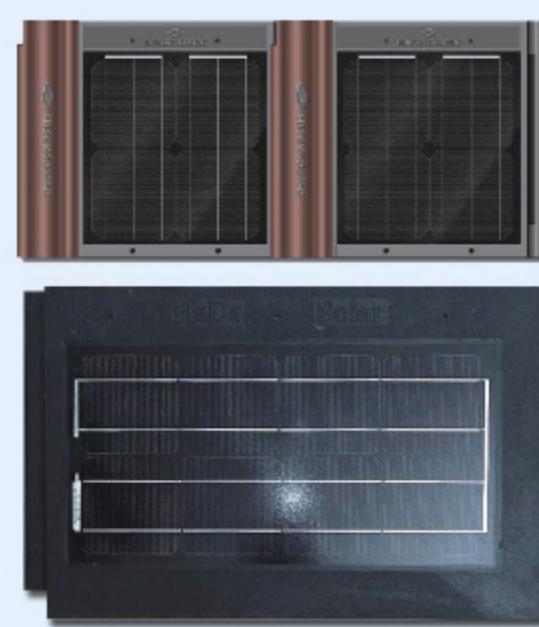


Filter Orientation Technology

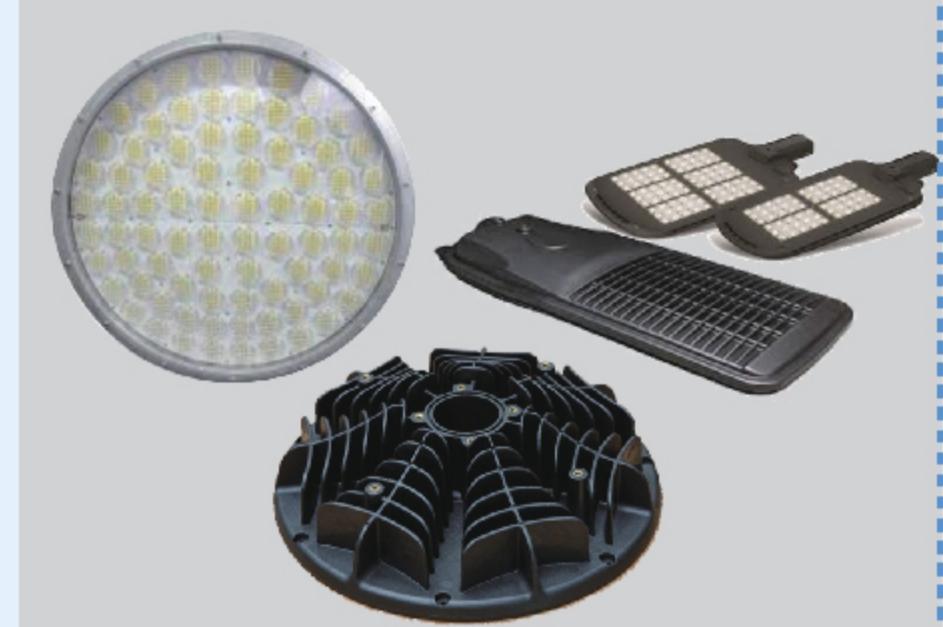
Applications



Thermal Compounds



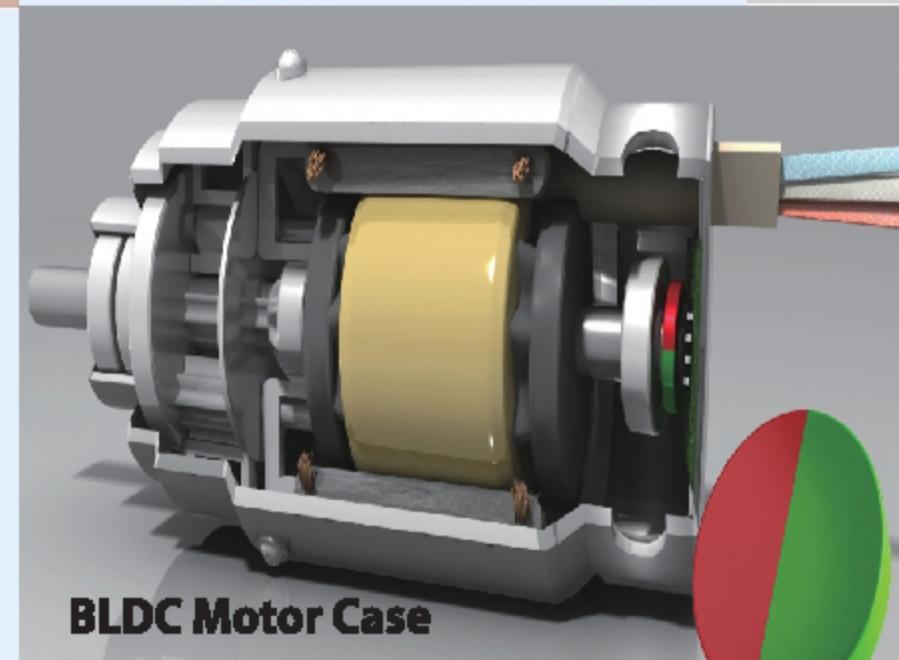
Solar cell



LED Heat sink



EV-Battery Case



BLDC Motor Case

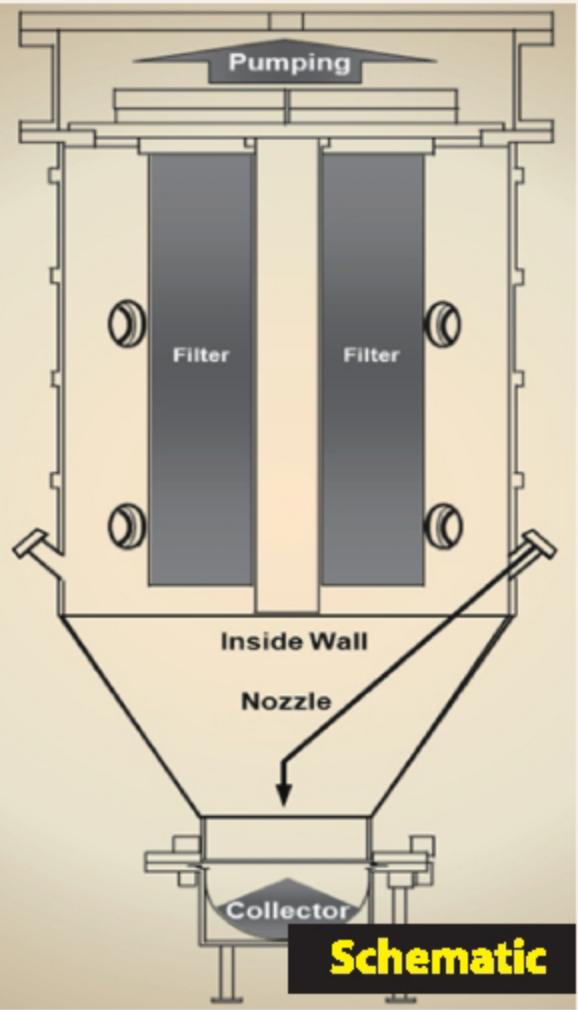


Sensor Motor

03 Powder Functional Plasma System

Filter Adsorption Type

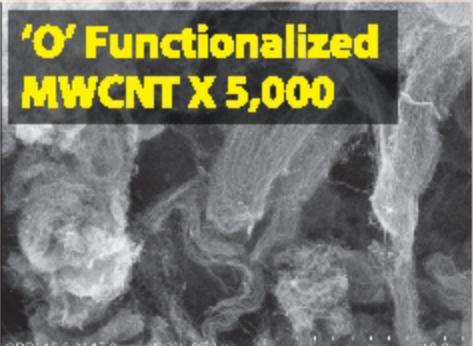
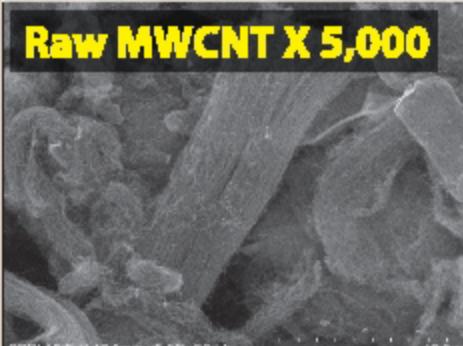
Plasma Powder Treatment System



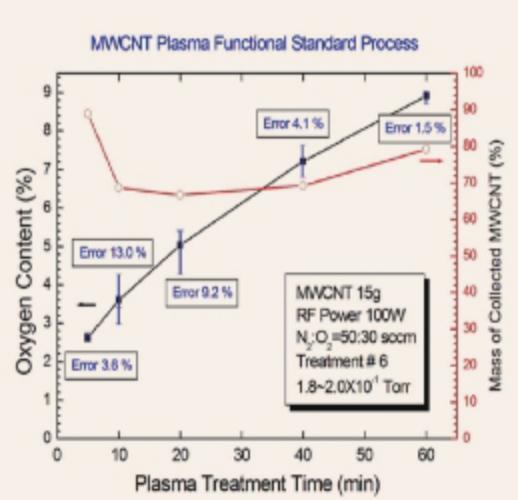
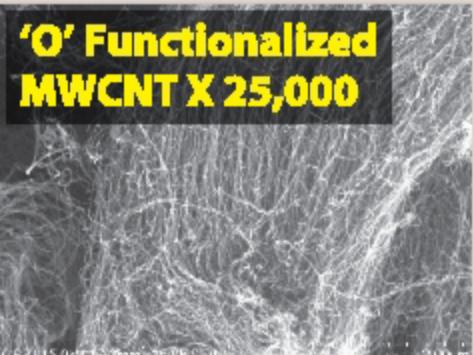
Real Image

Schematic

- Size : 1000(W) x 2000(D) x 2300(H)
- Radio Frequency Power (Max. 250W)
- Volume of Chamber : ~245.5L
- Mass Flow Controller System
- Rotary Pump Vacuum Condition
- 4 Adsorption Metal Filters
- Functionalized Powder Yield Rate : 80~90%
- High Performance Uniformity (>90%)



Functionalized powder image change



Oxygen-functionalized MWCNT



special feature

- Almost Powder can be processed
- Highly Functional Process
- Almost 70~90% Powder Collected
- Cycling Repeat Process

Circulating Type

Atmospheric Pressure Plasma



specification

- | | |
|------------------------|---------------------------|
| • Gliding Arc | • Reservoir Volume : 25 L |
| • Powder Circulation | • Power : 1.5 kw |
| • Repetition Treatment | • Blower Speed Control |

	X 10,000	X 25,000	X 50,000	X 100,000
Untreated				
Plasma treated				

Uniformly distributed Ni particles on graphite surface After the plasma treatment



Mapping C-Red, O-Blue, Ni-Green

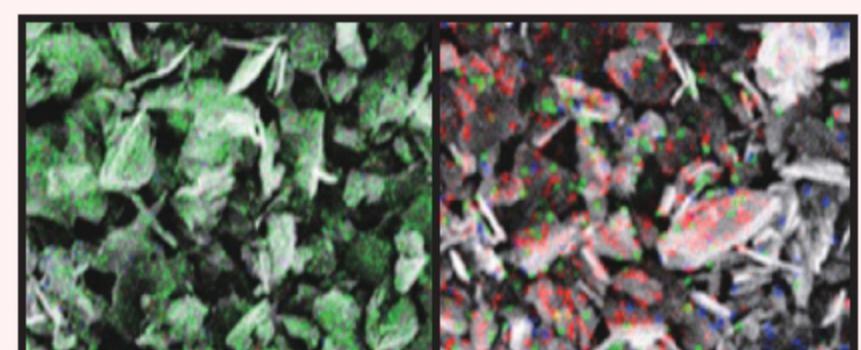


Image Mapping of O, C, Ni, after the plasma treatment, Functional O distributed generally edge of graphene.

Plasma Discharge

special feature

- Production 0.5 kg/hr for MWCNT
- Production 1 kg/hr for Graphene
- Production 10 kg/hr for Ceramic

04 LED/OLED ICT Convergence Research Center

Facility for OLED & LED Lighting



OLED/LED Lighting Technology

OLED Lighting Technology

	OLED Structure	Lighting Extraction Film Structure	Performance			
			Name	Efficiency (mW)	CRI	CCT
Normal WOLED	 Normal WOLED	 Only improvement of Light extraction	WOLED Bare	100%	78	2,268
			WOLED + Normal Film	150%	75	2,495
CPRI WOLED	 CPRI WOLED	 Improvement of not only Light extraction but also CRI Simultaneously	WOLED + CPRi Film	150%	87	2,130

LED Lighting Technology

	Structure	CRI	Light distribution
Direct ED Lighting (Normal)	 PKG Technology	 Low CRI (Low Thermal Stability)	 Total Lumens Flux = 123,369 Lumens Efficiency = 57.00lm/W
Diffused Indirect LED Lighting (GLV)	 Nano Film Technology	 High CRI (High Thermal Stability)	 Total Lumens Flux = 105,849 Lumens Efficiency = 62.20lm/W